AMENDMENTS TO THE CLAIMS

1. (Currently amended) A plasma display panel (PDP) adopting an AC surface discharge method comprising:

forming a front panel including:

a scan electrode and a sustain electrode both formed on a plate and to which a voltage is applied in order to generate discharge;

a dielectric layer covering the scan electrode and the sustain electrode; and

a protective layer formed on the dielectric layer, and

forming a back panel including:

an electrode protective layer covering an address electrode formed on a plate;

a barrier rib formed on the electrode protective layer; and

a phosphor layer provided between the barrier rib,

wherein the front panel and the back panel are arranged to oppose each other, and circumference thereof is sealed together so as to form a discharge space therebetween, and

wherein the protective layer on the dielectric layer is made of magnesium oxide (MgO) including silicon (Si) of which atoms count in a range from $5x10^{18}$ pieces/cm^3 to $2x10^{21}$ pieces/cm^3 and nitrogen (N) of which atoms count in a range from $1x10^{18}$ pieces/cm^3 to $8x10^{21}$ pieces/cm^3.

2. (Cancelled)

3. (Currently amended) A method of manufacturing a plasma display panel (PDP) adopting an AC surface discharge method, the method comprising the steps of:

forming a front panel including:

~~forming~~ a scan electrode and a sustain electrode both formed on a plate and to which a voltage is applied in order to generate discharge;

~~applying to the scan electrode and the sustain electrode a voltage in order to generate discharge; and~~

~~forming~~ a dielectric layer ~~to cover~~ covering the scan electrode and the sustain electrode; and

~~forming~~ a protective layer formed on the dielectric layer[[,]]; and

forming a back panel including:

an electrode protective layer covering an address electrode formed on a plate;

a barrier rib formed on the electrode protective layer; and

a phosphor layer provided between the barrier rib,

wherein the front panel and the back panel are arranged to oppose each other, and circumference thereof is sealed together so as to form a discharge space therebetween,

wherein ~~the step of~~ forming the protective layer on the dielectric layer includes [[is]] a process for forming a film that uses material of the protective layer, which material is made of magnesium oxide (MgO) including silicon (Si) and nitrogen (N), and

wherein a concentration of the Si falls within a range from 7 weight ppm to 8000 weight ppm, and a concentration of the N falls within a range from 4 weight ppm to 6000 weight ppm.

4. (Cancelled)

5. (Currently amended) [[The]] A method of manufacturing a PDP adopting an AC surface discharge method ~~as defined in claim 3~~, the method comprising the steps of:

forming a front panel including:

a scan electrode and a sustain electrode both formed on a plate and to which a voltage is applied in order to generate discharge;

a dielectric layer covering the scan electrode and the sustain electrode; and

a protective layer formed on the dielectric layer; and

forming a back panel including:

an electrode protective layer covering an address electrode formed on a plate;

a barrier rib formed on the electrode protective layer; and

a phosphor layer provided between the barrier rib,

wherein the front panel and the back panel are arranged to oppose each other, and circumference thereof is sealed together so as to form a discharge space therebetween, and

wherein forming the protective layer on the dielectric layer includes a process for forming a film that uses material of the protective layer, which ~~wherein the~~ material ~~of the protective layer~~ is made of magnesium oxide (MgO) including silicon nitride (Si_3N_4) of which concentration falls within a range from 10 weight ppm to 15000 weight ppm.

6. (Cancelled)

7. (Currently amended) ~~The material~~ Material of [[the]] a protective layer of a plasma display panel adopting an AC surface discharge method ~~as defined in claim 6~~, the plasma

display panel comprising a front panel including a scan electrode and a sustain electrode both formed on a plate and to which a voltage is applied in order to generate discharge; a dielectric layer covering the scan electrode and the sustain electrode; and a protective layer formed on the dielectric layer, and a back panel including: an electrode protective layer covering an address electrode formed on a plate; a barrier rib formed on the electrode protective layer; and a phosphor layer provided between the barrier rib, wherein the front panel and the back panel are arranged to oppose each other, and circumference thereof is sealed together so as to form a discharge space therebetween,

wherein the [[which]] material is made of magnesium oxide (MgO) including Si and N, wherein a concentration of the Si falls within a range from 7 weight ppm to 8000 weight ppm, and a concentration of the N falls within a range from 4 weight ppm to 6000 weight ppm.

8. (Currently amended) ~~The material~~ Material of [[the]] a protective layer of a plasma display panel adopting an AC surface discharge method ~~as defined in claim 6~~, the plasma display panel comprising a front panel including a scan electrode and a sustain electrode both formed on a plate and to which a voltage is applied in order to generate discharge; a dielectric layer covering the scan electrode and the sustain electrode; and a protective layer formed on the dielectric layer, and a back panel including: an electrode protective layer covering an address electrode formed on a plate; a barrier rib formed on the electrode protective layer; and a phosphor layer provided between the barrier rib, wherein the front panel and the back panel are arranged to oppose each other and circumference thereof is sealed together so as to form a discharge space therebetween, and

wherein the [[which]] material is made of magnesium oxide (MgO) including silicon nitride (Si_3N_4) of which concentration falls within a range from 10 weight ppm to 15000 weight ppm.